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		http://www.eletel.p.lodz.pl
Institute of Electronics of the Technical University of Lodz		<u>1</u>
Manager:	potential promoters:	contact person:
Sławomir Hausman, PhD, DSc	Sławomir Hausman, PhD, DSc	Sławomir Hausman, PhD, DSc Phone: +48 42 631-26-36 slawomir.hausman@p.lodz.pl
 scope of activity: Modelling with full-wave simulation methods and design of 2D and 3D electromagnetic metamaterials; Circuit-equivalent models of resonator arrays for effective optimisation, e.g. frequency band broadening of EBG or AMC materials; 		graphic material
 Development of optimised algorithms for printing gradient 3D dielectric metamaterials with complex internal structures, bypassing typical (but print quality-limiting) data formats such as STL; Design and optimisation (using genetic algorithms) of metamaterial structures for applications such as flat lenses (dielectric or with resonating structures), artificial magnetic conductors (AMC) or band gap structures (EBG); Development of effective modeling methods for metamaterials with resonant structures. 		
future actions: - Development of methods to co - Development of terahertz-ban	ntrol the parameters of metamaterials by means o d metamaterials.	f light or other factors;
publications/patents/awards/grants:		
 Hausman S., Jopek L., "Tunable Flat MRI Lens", on International Symposium on Electromagnetic Fields in Mechatronics, Electrical and Electronic Engineering, Nancy, France, 2019. Jopek, L., Hausman, S., Barba, P.D. : "Optimization of an Artificial Magnetic Conductor Geometry Using a Paretian 		
Approach", 13th European Conference on Antennas and Propagation, EuCAP 2019.		
keywords: metamaterials, gradient metamater terahertz gap	ials, metasurfaces, artificial magnetic conductor, c	omputational electromagnetcs,
a list of proposals for traineeships in the research group concerned:		
Development of methods for the:		
 design and manufacturing of gradient metamaterials; design of metasurfaces, including metasurfaces with parameters that change under the influence of light or other factors. 		